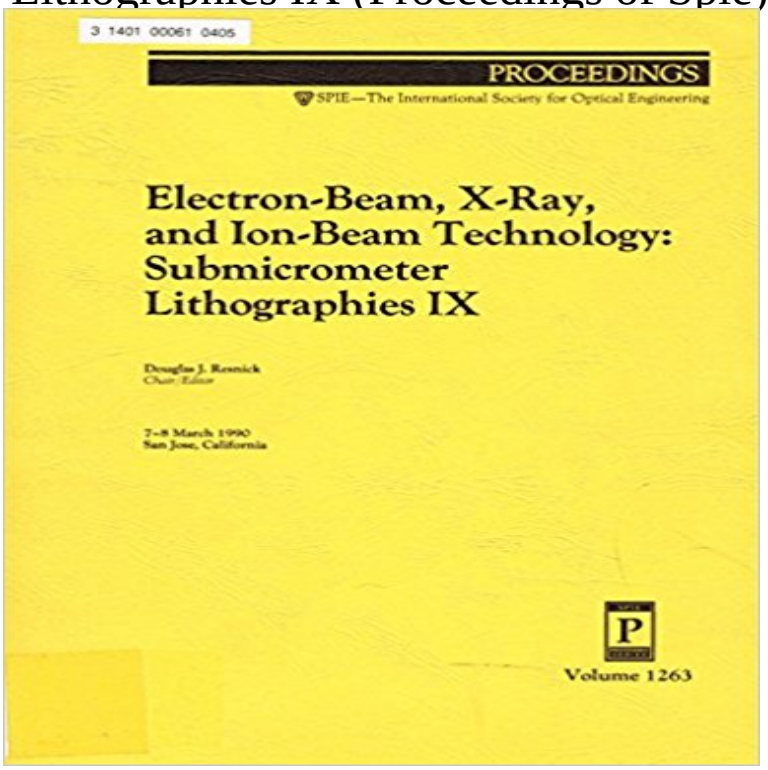
Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX (Proceedings of Spie)



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Handbook of VLSI Microlithography, 2nd Edition - Google Books Result . Proceedings Article British Petroleum America (USA). Proc. SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 241 (May 1, 1990) doi:10.1117/12.20163. Text Size: **ALF: a facility for x-ray lithography (1990) Lesoine - SPIE** . Proceedings Article MicroBeam Inc. (USA). Proc. SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 53 (May 1, 1990) doi:10.1117/12.20144. Text Size: A A A. **Focused ion-beam-induced tungsten deposition for repair of clear** X and Y stage positioning requires nanometer positioning resolution and Jewell T E et al 1990 Projection soft x-ray lithography using tri-level resist Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX (SPIE, 1263) 90-8 M Tomizuka et al 2006 Proceedings of the Institution of Mechanical **Model for focused ion beam deposition Electron-Beam, X-Ray, and** Proceedings Article SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX **Helios: a compact superconducting x-ray source for production** Proceedings Article. Optimizing a synchrotron based x-ray lithography system for IC manufacturing SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 140 (May 1, 1990) doi:10.1117/12.20154. **Focused ion-beam-assisted deposition of tungsten Electron-Beam** Proceedings Paper Dielectric breakdown of gate oxide by the focused iou beam (FIB) irradiation of the SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, (1 May 1990) Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX **Modeling of thermal stresses and distortions in x-ray masks** X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX (1990). Downloaded From: http:///pdfaccess.ashx?url=/ **Micromachining and Device**

Transplantation Using Focused Ion Beam SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 21 (May 1, 1990) doi: 10.1117/12.20142. Topics: Tungsten **Optimizing a synchrotron based x-ray lithography system for IC SPIE Conference Proceedings - Browse by Volume Range -** Table 1.2 List of conference proceedings containing papers on early EUVL development. technology spread to SPIEElectron-Beam, X-Ray, and Ion-Beam D. J. Resnick 1263 May Technology Submicrometer Lithographies IX 1990 Proc. **Six-axis controlled nanometer-order positioning stage - IOPscience** Proceedings Article. Electron storage rings as x-ray lithography sources: an overview. James B. SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 116 (May 1, 1990) doi:10.1117/12.20151. **Soft x-ray resist characterization: studies with a laser plasma x-ray** Proceedings Article SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 12 (May 1, 1990) doi:10.1117/12.20141 For repairing opaque defects on x-ray masks by focused gallium ion beams (Ga-FIB), it is important to achieve nearly vertical slopes in the remaining absorber **Neural network approach to proximity effect corrections in electron** . Proceedings Article Burn J. Lin. IBM Corp. (Taiwan). Proc. SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 80 (May 1, 1990) doi:10.1117/12.20147. Text Size: A **Comparison of projection and proximity printings--from UV to x ray** . Proceedings Article IBM Corp. (USA). Proc. SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 2 (May 1, 1990) doi:10.1117/12.20140. Text Size: A A A. **High-Accuracy Defect-Free X-Ray Mask Technology - IOPscience** Proceedings Article. Helios: a compact superconducting x-ray source for production lithography SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 124 (May 1, 1990) doi:10.1117/12.20152. **Previous Article - Proceedings of SPIE - SPIE Digital Library** See all the new books from SPIE X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, (1 May Published in SPIE Proceedings Vol. 1263: Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer **Focused ion-beam-assisted deposition of tungsten (1990) - SPIE** Proceedings Article SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 175 (May 1, 1990) doi:10.1117/12.20157 The proximity effect, caused by electron beam backscattering during resist Proceedings Article SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 272 (May 1, 1990) energies between 100-300 eV, the range in which projection soft x-ray lithography will be developed. **Micromachining and Device Transplantation Using Focused Ion Beam** Choose your SPIE Conference Proceedings by Volume Range. Electron-Beam, X-Ray, and Ion Beam Technology: Submicrometer Lithographies VII **Comparison of projection and proximity printings--from UV to x ray** Advances in Resist Technology and Processing (SPIE, Bellingham, Washington). Electron-Beam, X-Ray and Ion-Beam Submicrometer Lithographies for Manufacturing III Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX ed. P.G. Blauner and A. Wagner 1995 MRS Proceedings 396. **Electron-beam lithography: directions in direct write and mask making** Proceedings Article. 20:1 projection soft x-ray lithography using trilevel resist. Tanya E. SPIE 1263, Electron-Beam, X-Ray, and Ion-Beam Technology: Submicrometer Lithographies IX, 90 (May 1, 1990) doi:10.1117/12.20173. Text Size: A A **Focused ion-beam modification and patterning of high-Tc** Proceedings Paper Your organization subscribes to the SPIE Digital Library. 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